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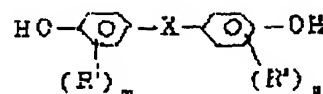
## (54) PRODUCTION OF HIGH-PURITY DI-ALKALI METALLIC SALT OF BISPHENOL

(57)Abstract:

**PURPOSE:** To obtain an anhydrous uniform solution of the titled high-purity compound having an extremely low content of mono-alkali metallic salt substantially in an anhydrous state, by reacting a specific amount of a bisphenol alkali metallic salt-forming agent with a specific bisphenol.

**CONSTITUTION:** A bisphenol shown by formula (X is SO<sub>2</sub>, CO, O, S, 1W6C alkylene and alkylidene, 5W15C cycloalkylene and cycloalkylidene; R<sub>1</sub> and R<sub>2</sub> are 1W3C alkyl and alkoxy, F, Cl or Br; m and n are 0W4) is reacted with 0.1W0.8 excess based on OH of the bisphenol of a bisphenol alkali metallic salt-forming agent such as KOH in an inert organic polar solvent so that the amount of mono-alkali metallic salt of bisphenol is ≤0.2mol and water in the system is removed to give the aimed compound useful as a raw material for polycondensation polymer, etc.

**EFFECT:** Is especially useful for raising molecular weight of polystyrene.



## LEGAL STATUS

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